

Form PTO-1449 (modified)

List of Patents and Publications for Applicant's

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Atty. Docket No.

97-0008.02

Serial No.

Unknown

Applicant

Bradley J. Howard

Filing Date:

Herewith

Group:

Unknown

U.S. Patent Documents

See Page 1

Foreign Patent Documents

N/A

Other Art

See Page 1

U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date if App.
SJL	A1	4,921,321	5/1/90	Weidman	385	130	
	A2	5,439,780	8/8/95	Joshi et al.	430	296	
	A3	5,215,861	6/1/93	Augustino et al.	430	210-1	
	A4	4,978,594	12/18/90	Bruce et al.	430	14	
✓	A5	5,885,751	3/23/99	Weidman et al.	430	315	

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
SJL	C1	Ajey M. Joshi et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography," <i>SPIE</i> , Vol. 1925, pp. 709-720, January 1993.
	C2	O. Joubert et al., "Plasma polymerized - dry resist process for 0.25 μ m photolithography," <i>J. Vac. Sci. Technol. B</i> 12(6), pp. 3909-3913, Nov/Dec 1994.
	C3	O. Joubert et al., "Plasma Polymerized Organosilane Network Polymers; High Performance Resists for Positive and Negative Tone Deep UV Lithography," <i>SPIE</i> , Vol. 2195, pp. 358-371, May 1994.
	C4	T. W. Weidman et al., Applications of Plasma Polymerized Methylsilane as a Resist and Silicon Dioxide Precursor for 193 and 248 nm Lithography," <i>SPIE</i> , Vol. 2438, pp. 496-512, June 1995.
✓	C5	Timothy W. Weidman and Ajey M. Joshi, "New photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers," <i>Appl. Phys. Lett.</i> 62(4), pp. 372-374, January 25, 1993

Examiner:

Date Considered:

12-12-04

EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.